

Development of New Non-chemically Amplified Resists for High-resolution Lithography Applications

A thesis

submitted by

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(D14010)

for the award of the degree of

DOCTOR OF PHILOSOPHY



SCHOOL OF BASIC SCIENCES

INDIAN INSTITUTE OF TECHNOLOGY MANDI

KAMAND-175005 (H.P.), INDIA

July, 2018

**DEDICATED TO "ALL MY LOVED ONES" AND
MOTHERLAND "INDIA"**



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Declaration by the Research Scholar

This is to certify that the thesis entitled “**Development of New Non-chemically Amplified Resists for High-resolution Lithography Applications**”, submitted by me to the Indian Institute of Technology, Mandi for the award of the degree of Doctor of Philosophy is a bonafide record of research work carried out by me under the supervision of **Dr. Pradeep C. Parameswaran**. The contents of this thesis, in full or in parts, have not been submitted to any other Institute or University for the award of any degree or diploma.

In keeping with the general practice of reporting scientific observation, due acknowledgements have been made wherever the work described is based on the findings of other investigators.

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Thesis Certificate

This is to certify that the thesis entitled “**Development of New Non-chemically Amplified Resists for High-resolution Lithography Applications**”, submitted by **Mr. P. Guru Prasad Reddy** to the Indian Institute of Technology, Mandi for the award of the degree of Doctor of Philosophy is a bonafide record of research work carried out by him under my supervision. The contents of this thesis, in full or in parts, have not been submitted to any other Institute or University for the award of any degree or diploma.

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Acknowledgements

I would like to express my deep sense of thanks and heartiest gratitude to my thesis advisor **Dr. Pradeep C. Parameswaran** for his continuous guidance, encouragement, suggestions, and love throughout the tenure of my Ph.D. This thesis would not have been possible without his inspiration and support. His punctuality, professionalism, leadership qualities and helping nature have always inspired me to do more and become like him. During difficult times, he was always there to push me towards success. It was a great honor and wonderful experience for me to work with him.

I would like to thank **Prof. Kenneth E. Gonsalves** and his interdisciplinary team consisting of **Dr. Subrata Ghosh**, **Dr. Satinder Kumar Sharma** and **Dr. Pradeep C. Parameswaran** for introducing me to the field of nano-lithography. Under their guidance, I could learn a lot about this emerging area and I am grateful to all of them for their generous contributions towards my research work.

I would like to acknowledge the following research projects which funded my Ph.D work during initial years:

- Development of Polyoxometalates-Organic hybrids having 'through-bond' electronic interactions between cluster and organic units for materials and catalytic applications' (DST Fast Track Project: No. SR/FT/CS-58/2011).
- Resists concepts for EUVL at the 16 nm node and beyond. (From INTEL/SEMATECH, United States of America).
- Next generation, cutting-edge indigenous EUVL resist technology for semiconductor industry. (From DST-TSDP, India)
- Novel non-chemically amplified molecular photoresists for nanoelectronics at the 20 nm node or beyond. (From DST-GITA, India)

I express my sincere thanks to the Doctoral Committee members **Dr. Venkata Krishnan**, **Dr. Abhimanew Dhir**, **Dr. Hari Varma** and **Dr. Mohammad Talha** for their valuable time, efforts and suggestions towards my thesis work.

ACKNOWLEDGEMENTS

I would like to thank the Director, IIT Mandi (*Prof. Timothy A. Gonsalves*) for his support and motivation and also for providing us with the excellent research facilities at IIT Mandi through the Advanced Materials Research Center (AMRC). My sincere thanks are also due to all the Chemistry faculty members, especially, *Dr. Prem Felix Siril, Dr. Chayan K. Nandi, Dr. Aditi Halder and Dr. Rik Rani Koner* for their constant support throughout my Ph.D tenure.

I would like to thank my lab mates and friends at IIT Mandi for their encouragement and moral support which made my stay and studies more enjoyable. I would like to thank *Venky, Rambabu, Prateep, Nagaraju, Lingeswar Reddy, Yogesh, Ravi, Dr. Rajesh chebolu* and *Rajkumar* for being great friends and for their continuous help during my Ph.D. work. I would like to thank my brother *Dr. V. S. V. Satynarayana* for his continuous efforts to make me an independent researcher at the initial stages of my Ph.D.

Big thanks to all my colleagues and friends, particularly, *Manisha, Abhishek, Ashwani (bana), Shilpa, Suman, Ranjit, Aranya, Pankaj, Sunil, Reena, Sougata, Bulti, Tripti, Suneel, Vipul, Navneet Chandra Verma, Syamantak, Harpreet, Lalitha, Trivender, Ashish, Gourab, Santu, Neha, Pawan, Moinuddin and Shivani* for providing me a friendly work environment. I would like to thank *Navneet Matharoo and Anjali* for working with me as project students. My sincere thanks to all the AMRC staff, particularly, *Dushyant, Sunil, Ishita, Pallavi, Puneet, Karam and Naresh* for their excellent assistance in the lab.

I would like to thank the Council of Scientific and Industrial Research (CSIR), India for a Senior Research Fellowship (SRF) at the final stage of my Ph.D program.

Finally, a special word of thanks to my ever loving family members *Bhogi Reddy, Shakuntamma, Jyothi and Venkateswara Reddy* for their continuous love, encouragement, motivation, patience, understanding and support throughout my life.

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